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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. .... 09/536,037  
Filing Date ..... March 27, 2000  
Inventor ..... Weimin (Michael) Li  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2822  
Examiner ..... T. Thomas  
Attorney's Docket No. .... MI22-1398  
Title: Low k Interlevel Dielectric Layer Fabrication Methods

PRELIMINARY AMENDMENT

To: Box RCE  
Assistant Commissioner for Patents  
Washington, D.C. 20231

From: Frederick M. Fliegel, Ph.D.  
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TC 2800 MAIL ROOMREMARKS

This Request for Continued Examination (RCE) Application is being filed in an abundance of caution to permit consideration of a Supplemental Information Disclosure Statement.

No new matter is being presented in this application.

Further, Applicant herewith submits a Supplemental Information Disclosure Statement and Form PTO-1449 of which it does not yet have an initialed copy from the Examiner. This Supplemental Information Disclosure Statement was initially submitted to the U.S. Patent and Trademark Office on November 15, 2001. To the extent the PTO-1449 has not already been initialed in the file, such examination and initialing is requested at this time, and returning of a copy

to the undersigned.

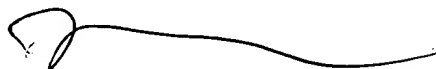
A telephonic interview is requested in the event that the next office action is one other than a Notice of Allowance. The undersigned is available during normal business hours (Pacific Time Zone).

Respectfully submitted,

Dated: \_\_\_\_\_

Nov 8, 2002

By: \_\_\_\_\_



Frederick M. Fliegel, Ph.D.  
Reg. No. 36,138